

Fig. 1

20022019856200T

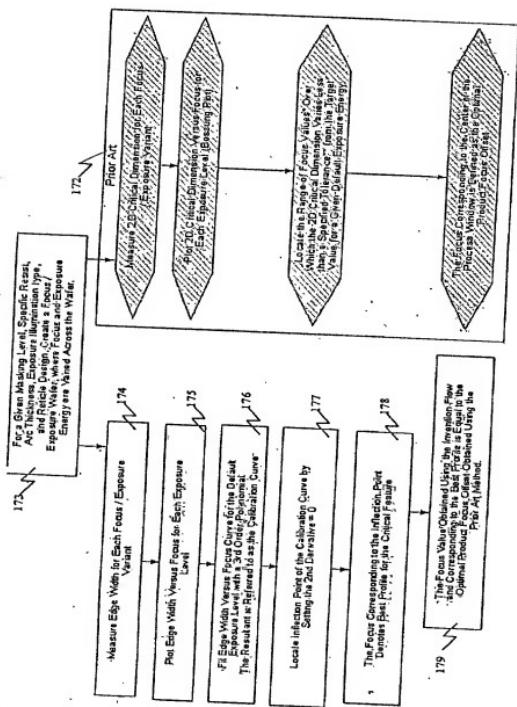


Fig. 1A

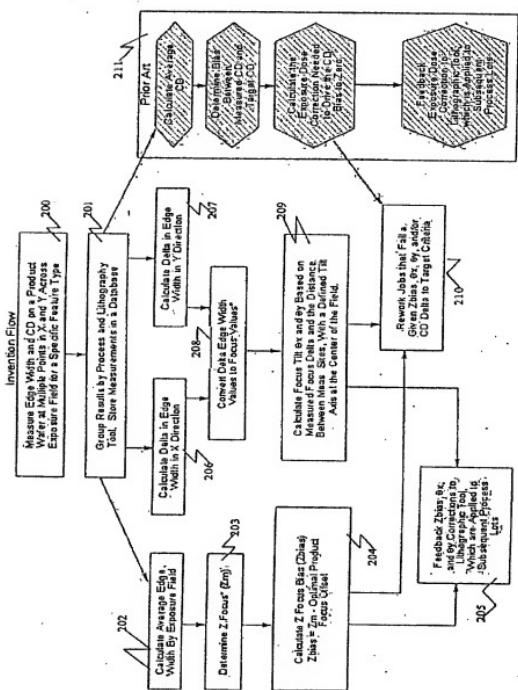
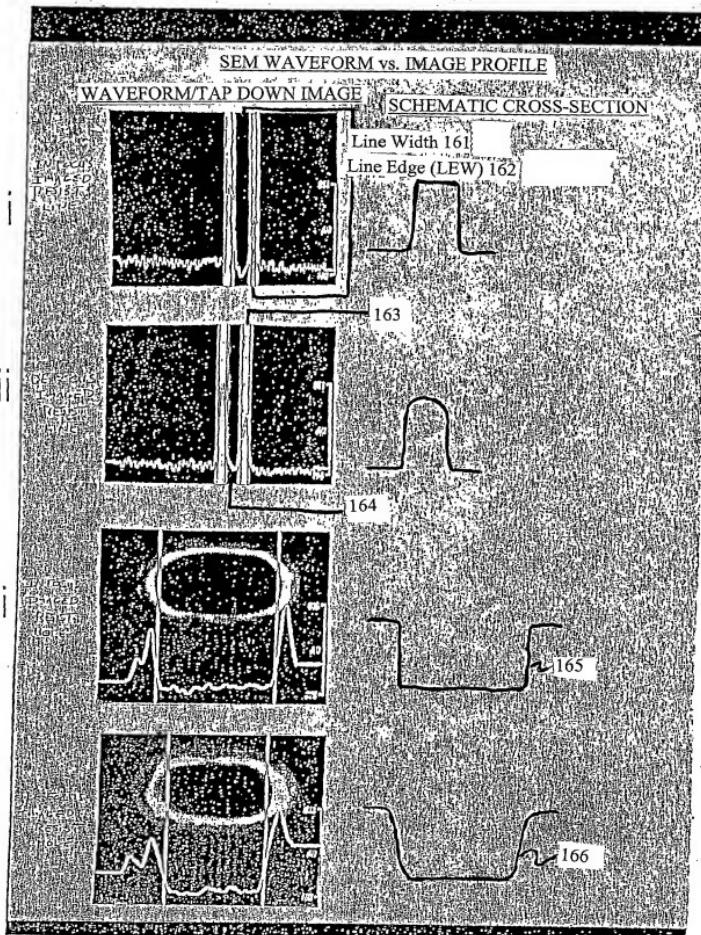


Fig. 1B



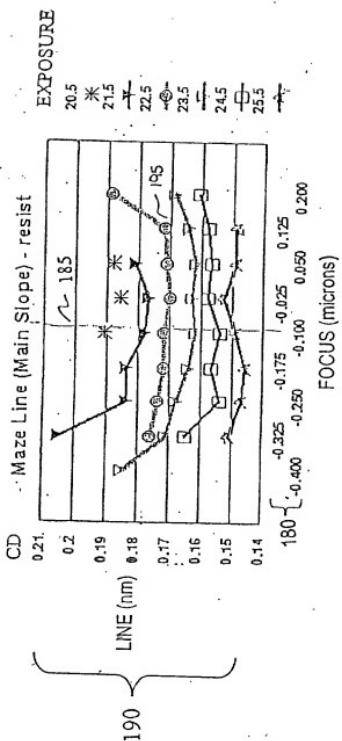


Fig. 1D

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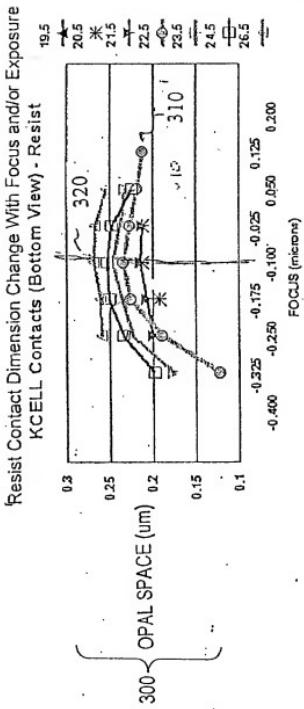


Fig. 2

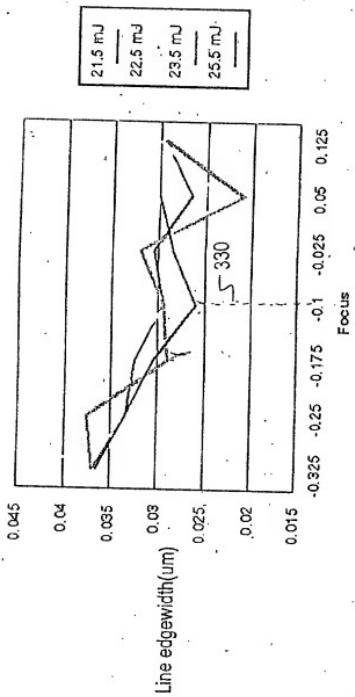


Fig 3

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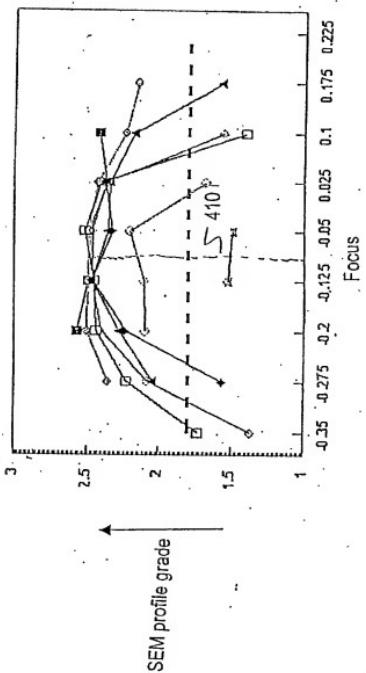


Fig. 4

Critical Dimension of Imaged Photoresist as Measured by CD

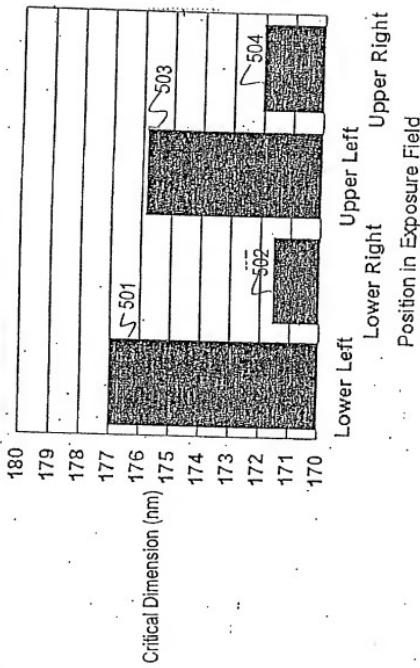


Fig. 5

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Line Edge Width of Imaged Photoresist as Measured by CD

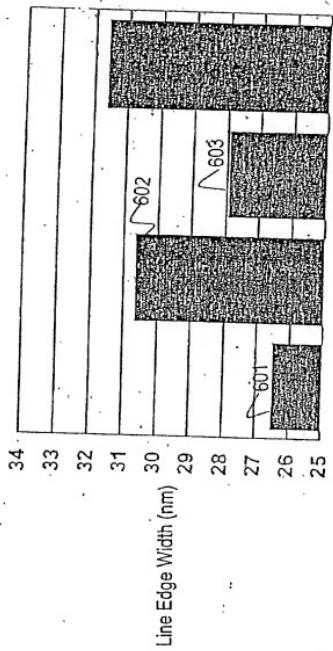


Fig. 6

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X/Y Tilt Determination Using Edge Width Measurement

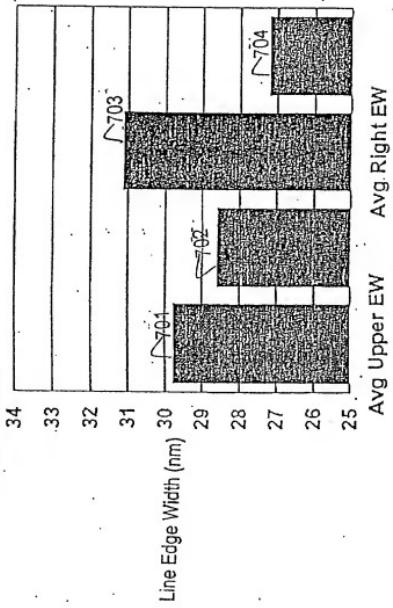


Fig. 7

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Edge Width vs. Focus

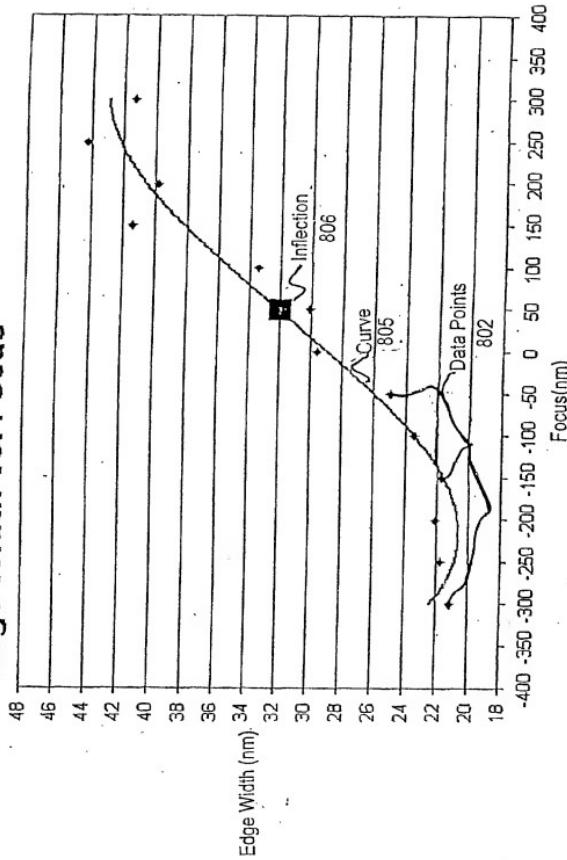


Fig. 8

autozu "6355zout

X/Y Tilt Determination Using Edge Width Measurement

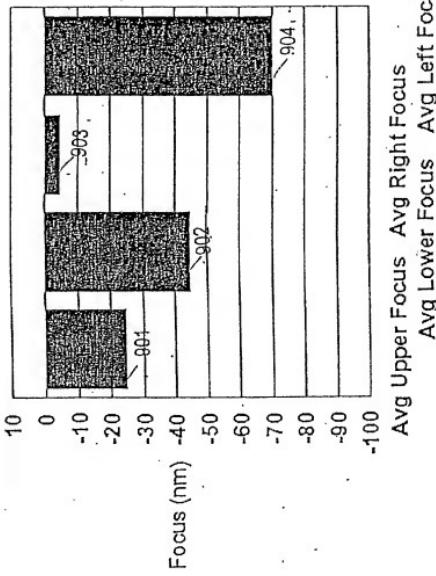


Fig. 9

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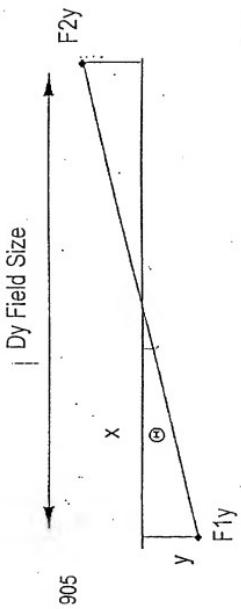


Fig. 10

200200 " 68867047

Tool Check Center of Focus vs Atmospheric Press

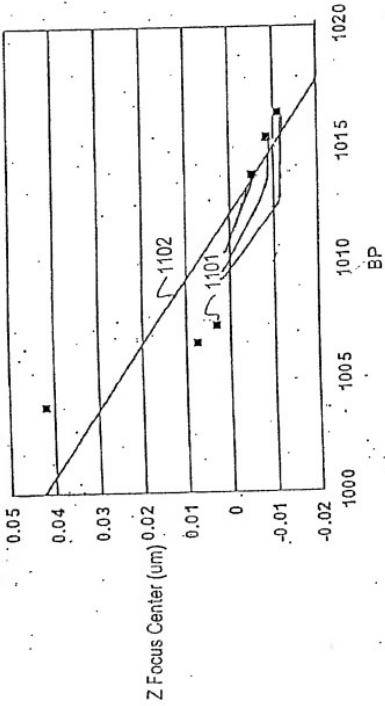


Fig. 11

20020 " 8866400T

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Edge Width vs Atmospheric Pressure

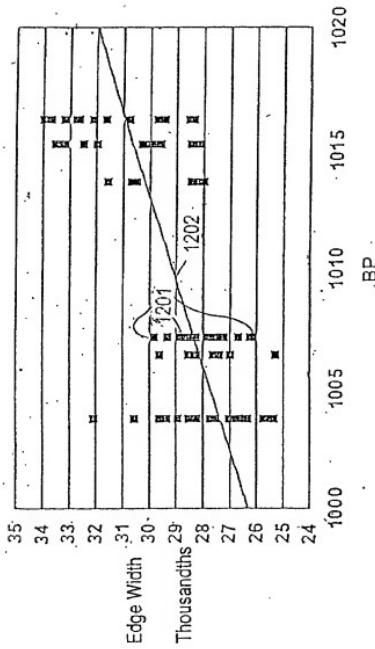


Fig. 12

TABLE OF RUN RULES

1310 Tool	1320 Technology	1330 WaferPN	1340 Process	1350 Opt	1360 Default Exposure	1370 Focus
U82V	ICE8S3D	*	MC	F	19.00	0.10
U82V	ICECB52	*	MC	F	19.00	0.10
U82V	ICECB53	*	MC	F	19.00	0.10
U84V	CMOS6X1	*	MC	F	20.00	0.00
U86V	CS019S0	*	MC9S	F	24.00	-0.10
U86V	CS019S0	0000008J0640	MC9S	F	30.00	-0.10
U86V	CS019S0	0000008J0645	MC9S	F	30.00	-0.10
U86V	CS019S0	0000057P6438	MC9S	F	28.00	-0.05
U86V	CS019S2	*	MC9S	F	25.00	-0.10
U92V	CS019S0	*	MC9S	F	24	-0.10
U92V	CS019S0	0000008J0639	MC9S	F	30.00	-0.10
U92V	CS019S0	0000008J0640	MC9S	F	30.00	-0.10

Fig. 13 (Prior Art)

200220 "635600T

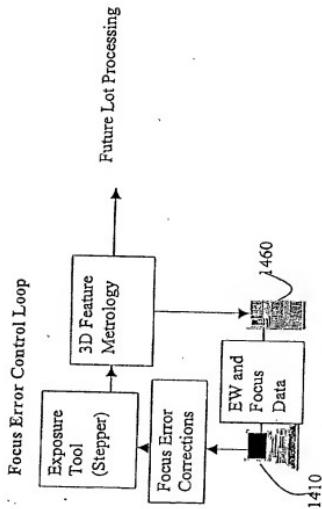


Fig. 14